

<b>Session Title:</b>	<b>[WA1] Nanoscale Thin Film Deposition VI</b>
<b>Session Date:</b>	<b>November 16 (Wed.), 2022</b>
<b>Session Time:</b>	<b>10:45-12:15</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Woongkyu Lee (Soongsil Univ., Korea)</b>

**[WA1-1] [Invited] 10:45-11:15**

**Atomic-Scale Manufacturing Using Selective Atomic Layer Deposition and Etching**

**Adrie Mackus (Eindhoven Univ. of Tech., Netherlands)**

**[WA1-2] 11:15-11:35**

**Inherently Area Selective Atomic Layer Deposition Toward Self-Aligned Atomic Level Patterning**

**Jeong-Min Lee (Hanyang Univ., Korea), Taewook Nam (Univ. of Colorado, USA), and Woo-Hee Kim (Hanyang Univ., Korea)**

**[WA1-3] 11:35-11:55**

**Inherently Area-Selective Atomic Layer Deposition of Device-Quality  $\text{Hf}_{1-x}\text{Zr}_x\text{O}_2$  Thin Films through Catalytic Local Activation**

**Jeong-Min Lee, Hyo-Bae Kim (Hanyang Univ, Korea), Yujin Lee (Stanford Univ., USA), Ji-Hoon Ahn, and Woo-Hee Kim (Hanyang Univ, Korea)**

**[WA1-4] 11:55-12:15**

**Strategy of Equipment Development for Next-Generation Devices based on MORE MOORE**

**Sang Hyun Ji, Pil Seong Jeong, and Chang Kyo Kim (AP System Corp., Korea)**